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(12) **United States Design Patent**
Koppa et al.

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(45) **Date of Patent:** **** Feb. 1, 2022**

(54) **PROCESS SHIELD FOR A SUBSTRATE PROCESSING CHAMBER**

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(**) Term: **15 Years**

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(51) **LOC (13) Cl.** **15-09**

(52) **U.S. Cl.**
USPC **D15/138**; D13/182

(58) **Field of Classification Search**
USPC D23/249, 259, 262, 269; D15/138, 139, D15/143, 144, 144.1, 144.2, 150, 199;
(Continued)

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(57) **CLAIM**

The ornamental design for a process shield for a substrate processing chamber, as shown and described.

DESCRIPTION

FIG. 1 is a top isometric view of a process shield for a substrate processing chamber, according to one embodiment of the novel design.

FIG. 2 is a bottom isometric view thereof.

FIG. 3 is a bottom plan view thereof.

FIG. 4 is a top plan view thereof.

FIG. 5 is a front elevation view thereof.

FIG. 6 is a back elevation view thereof.

FIG. 7 is a left side elevation view thereof.

FIG. 8 is a right side elevation view thereof.

FIG. 9 is cross-sectional view taken along line 9-9 of FIG. 3.

FIG. 10 is a top isometric view of a process shield for a substrate processing chamber, according to another embodiment of the novel design.

FIG. 11 is a bottom isometric view thereof.

FIG. 12 is a bottom plan view thereof.

FIG. 13 is a top plan view thereof.

FIG. 14 is a front elevation view thereof.

FIG. 15 is a back elevation view thereof.

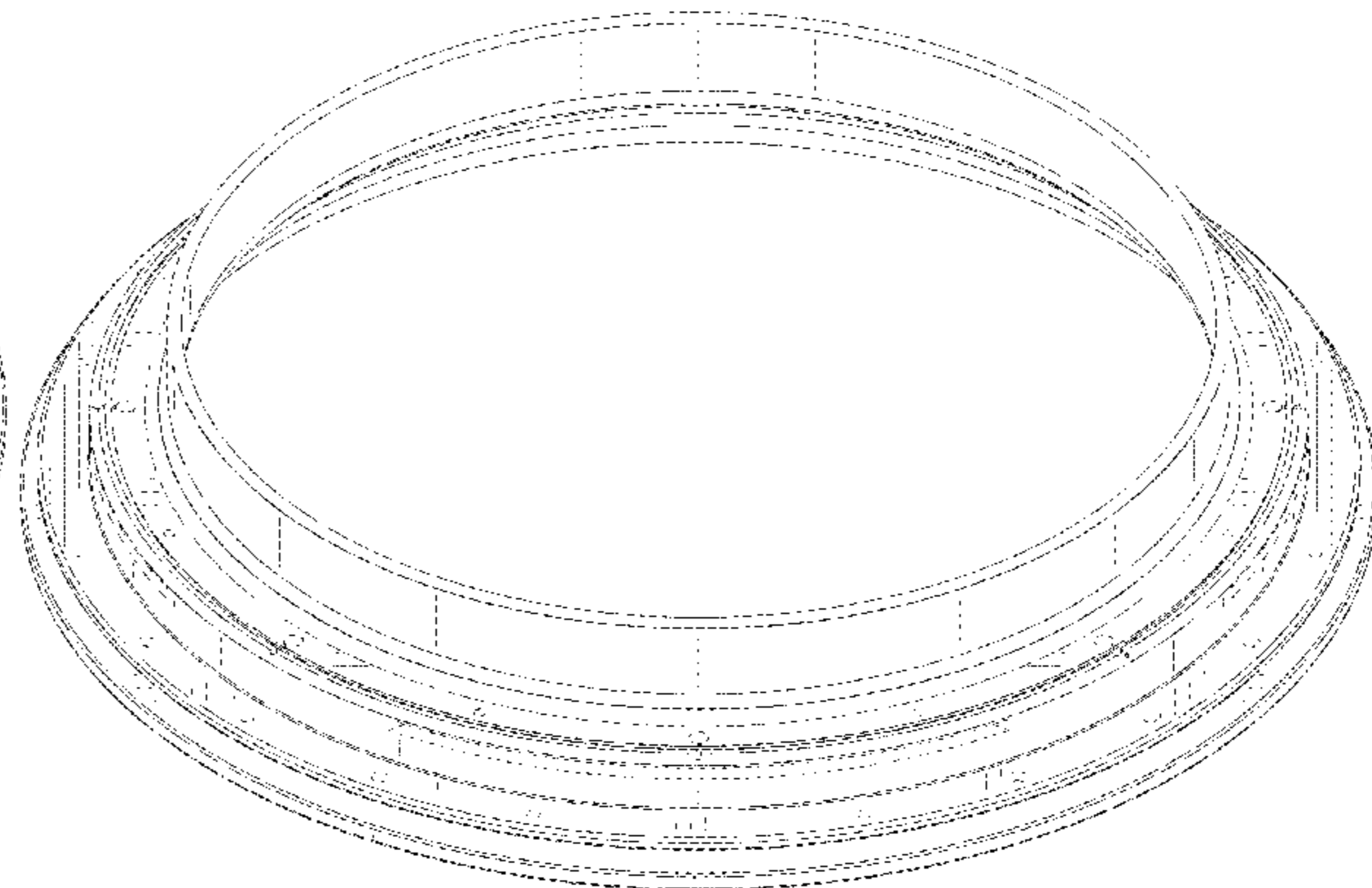
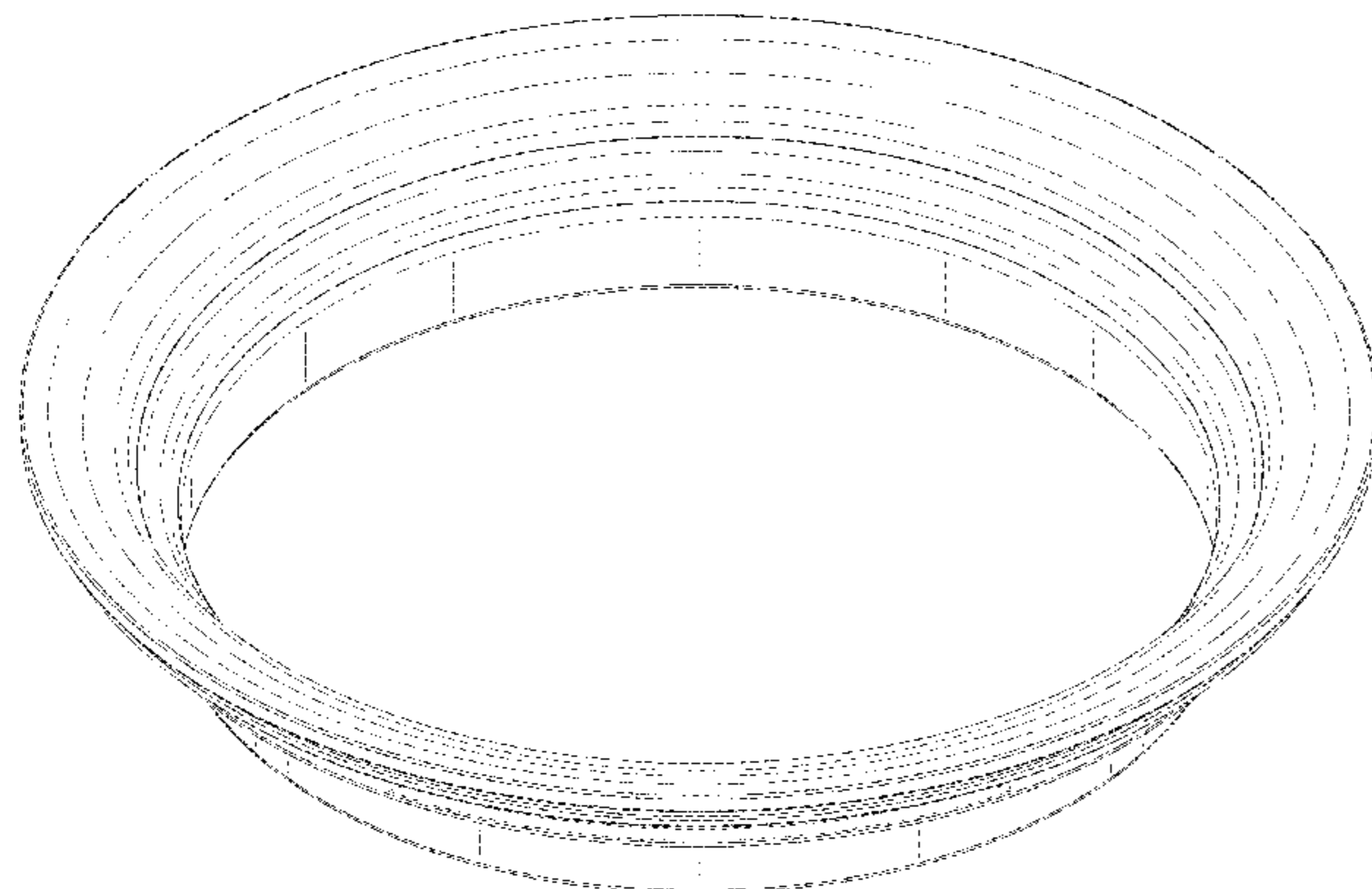
FIG. 16 is a left side elevation view thereof.

FIG. 17 is a right side elevation view thereof.

FIG. 18 is cross-sectional view taken along line 18-18 of FIG. 12; and,

FIG. 19 is cross-sectional view taken along line 19-19 of FIG. 14.

(Continued)



The dashed lines in FIGS. 1-19 represent unclaimed environment forming no part of the claimed design.

1 Claim, 19 Drawing Sheets

(58) **Field of Classification Search**

USPC D13/118, 122, 133, 162, 182, 184, 199;
D22/113, 119
CPC H01J 37/3414; H01J 37/3423; H01L
21/02631; H01L 2221/68363; H01L
2224/75186-75189; H01L 21/67742;
H01L 21/0226; H01L 21/02263; H01L
21/02266; H01L 21/02269; H01L
21/02271; F16J 7/00; E04D 13/14; C23C
14/3407; C23C 14/35

See application file for complete search history.

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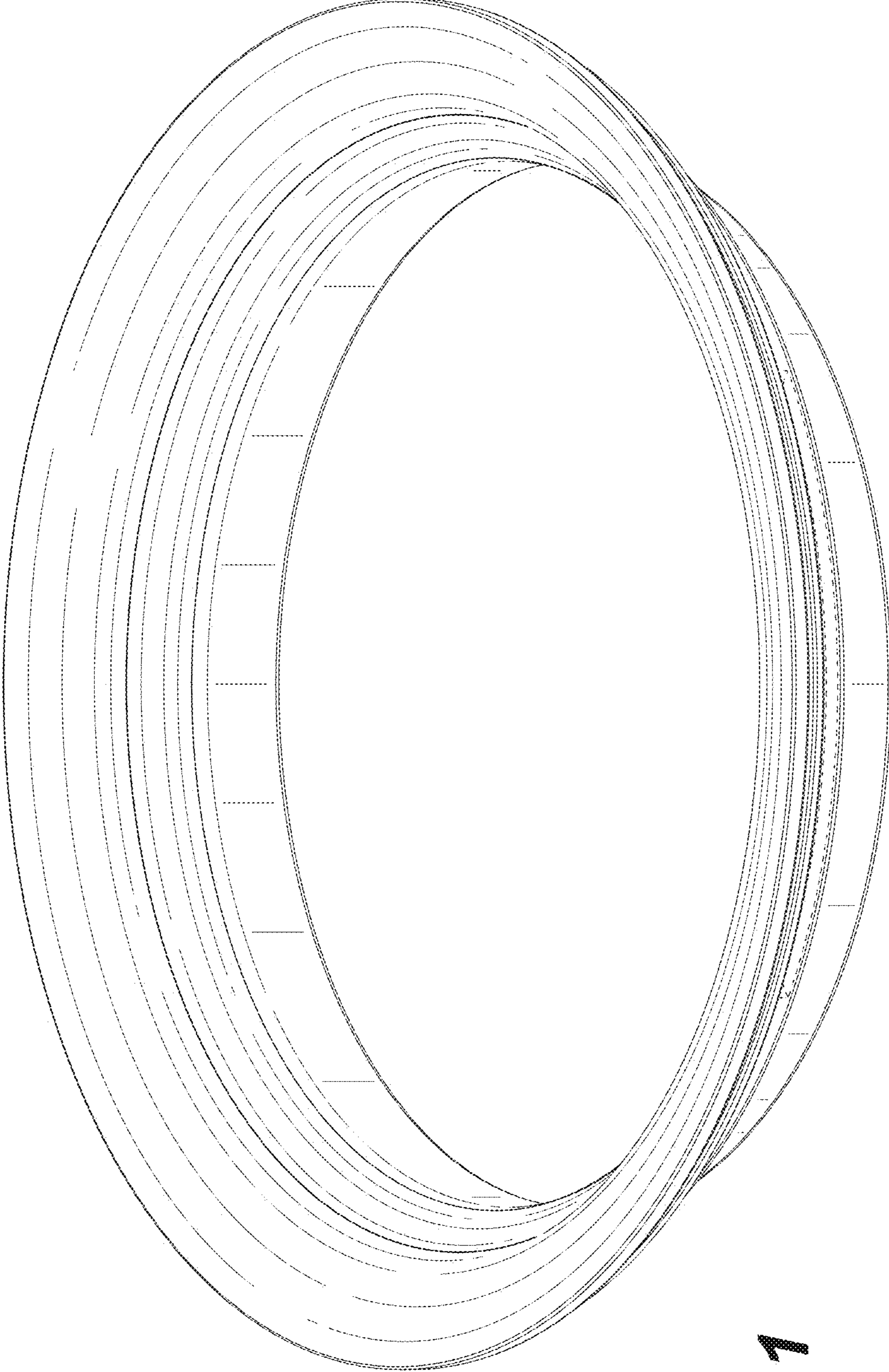


FIG. 1

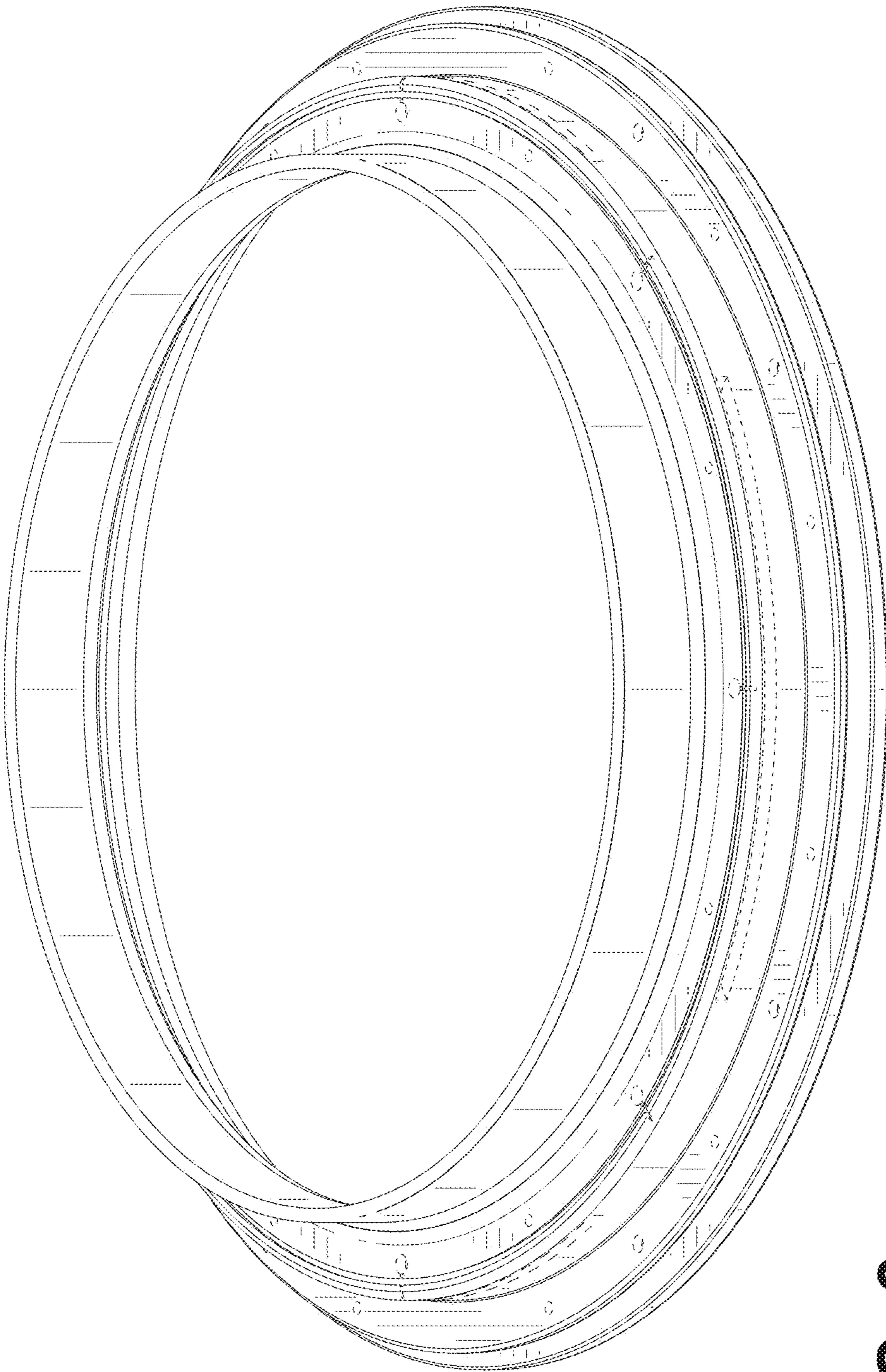


FIG. 2

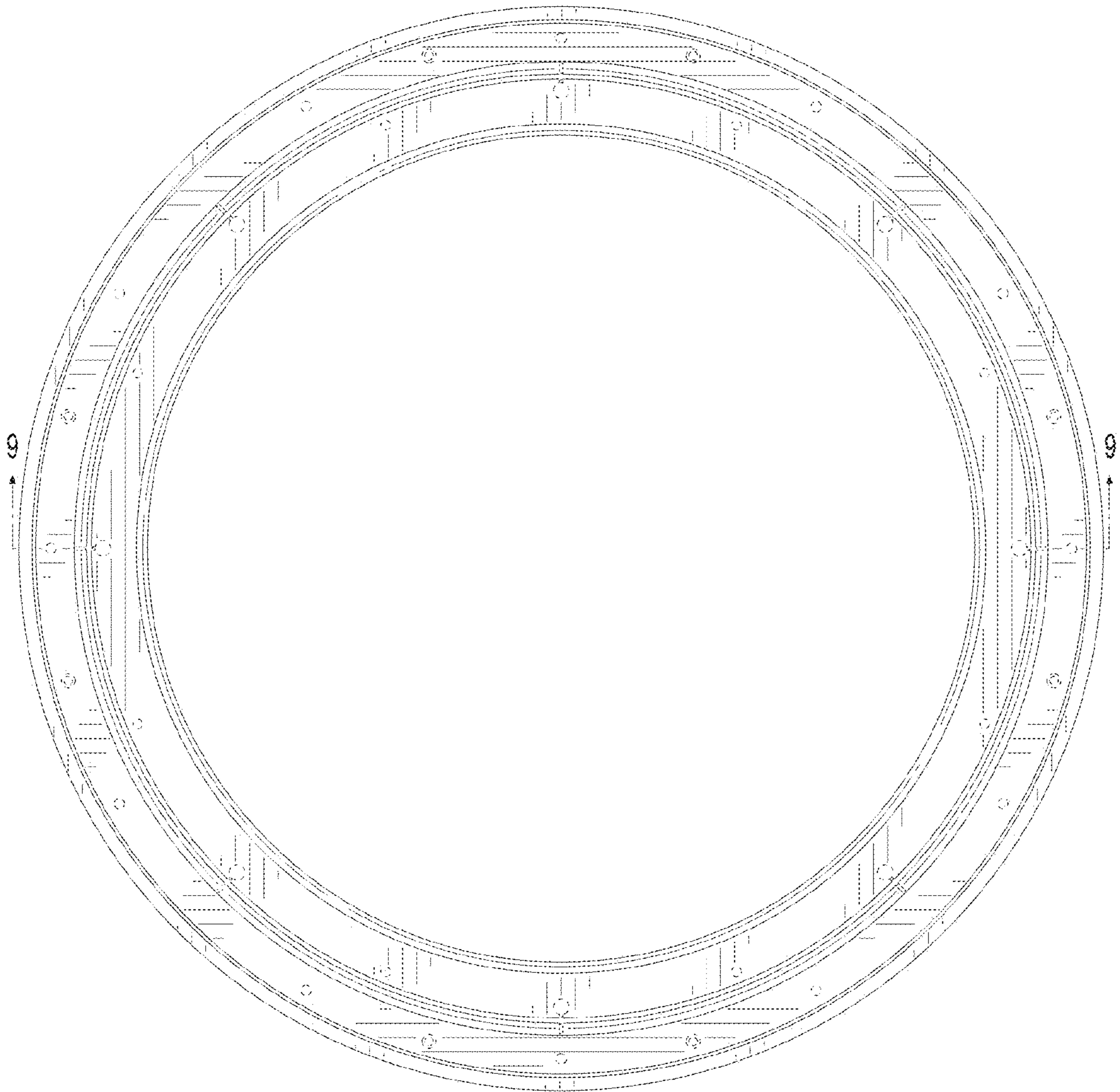


FIG. 3

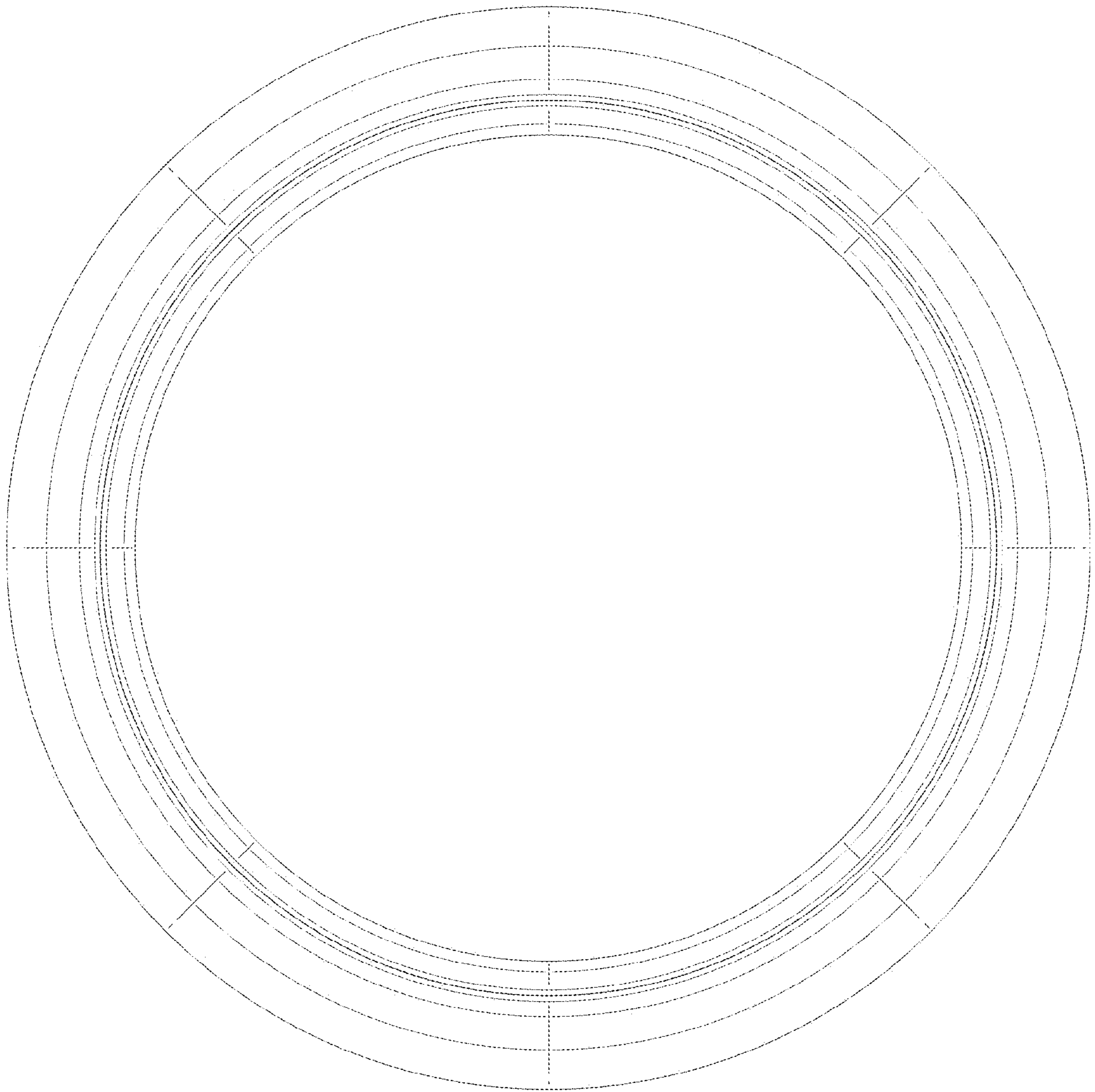


FIG. 4

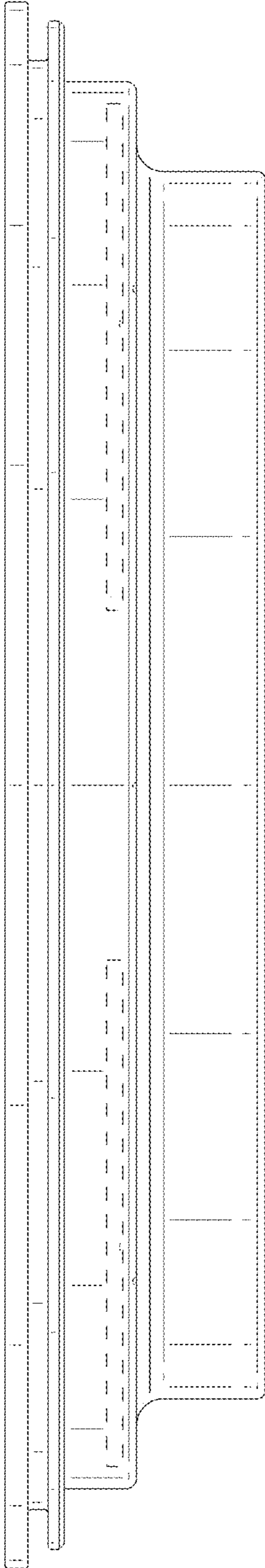


FIG. 5

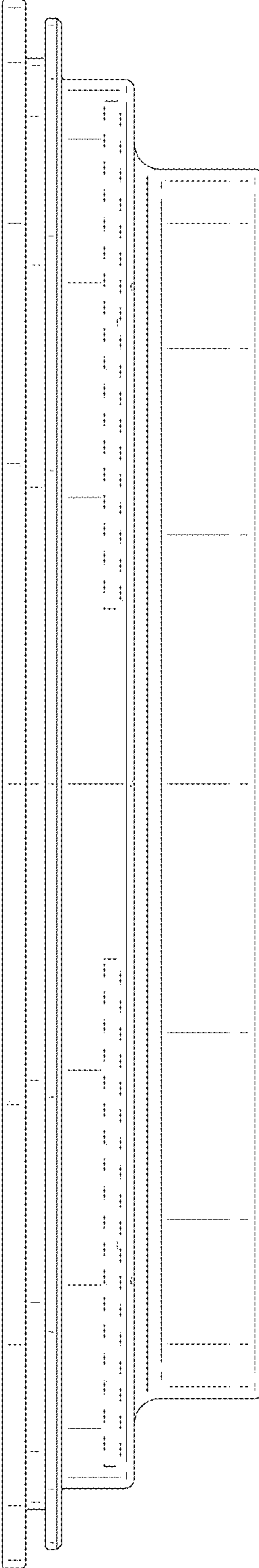


FIG. 6

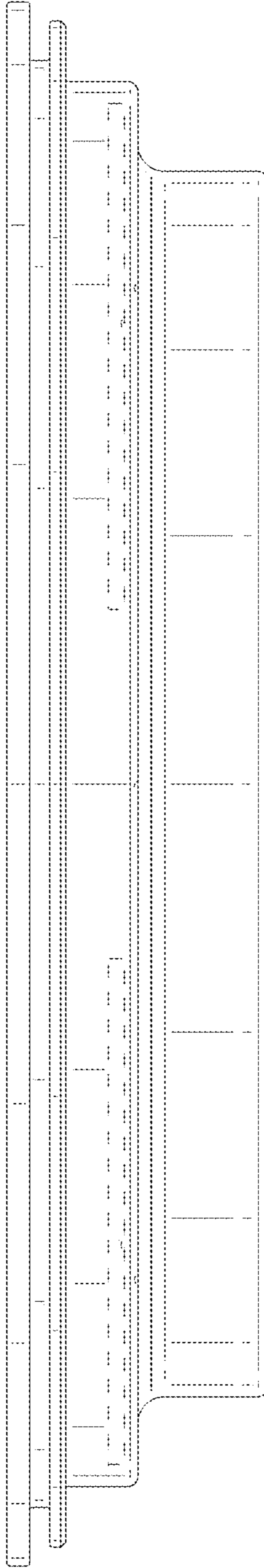


FIG. 7

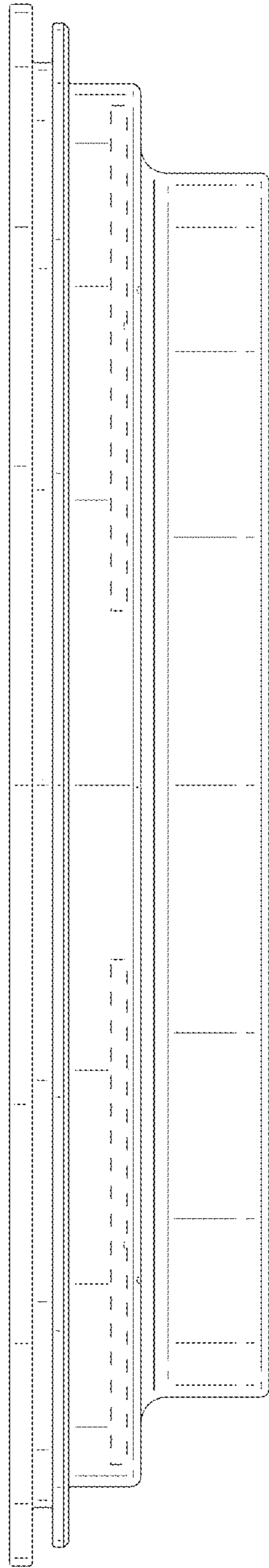


FIG. 8

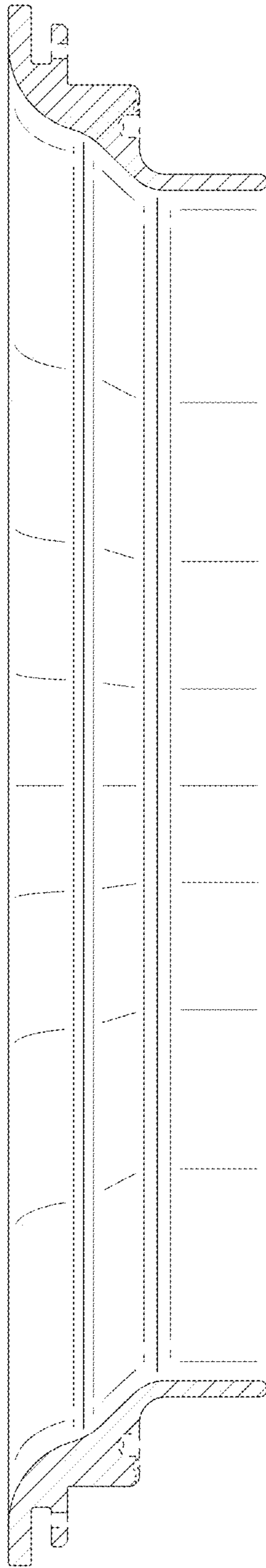


FIG. 9

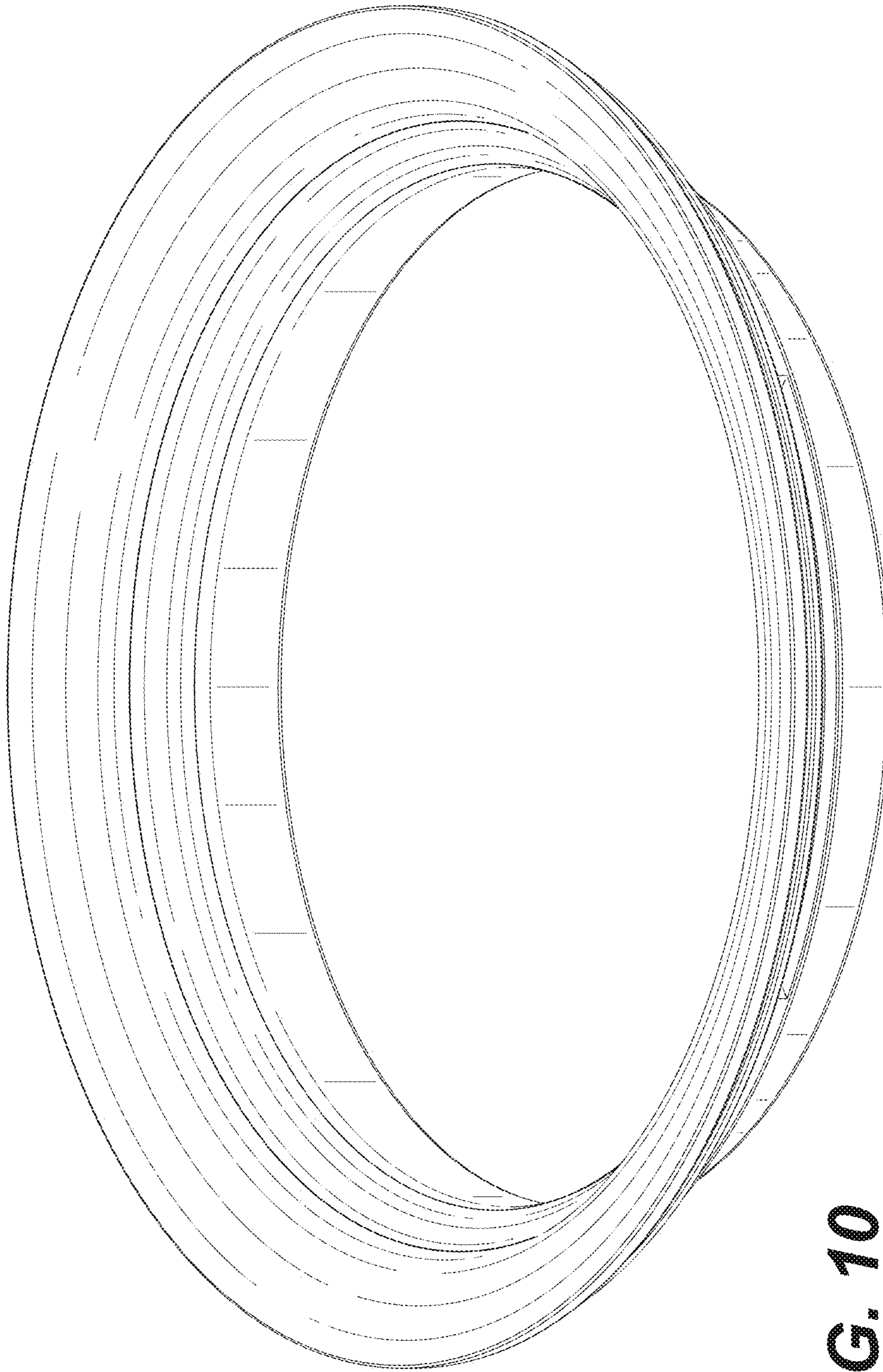


FIG. 10

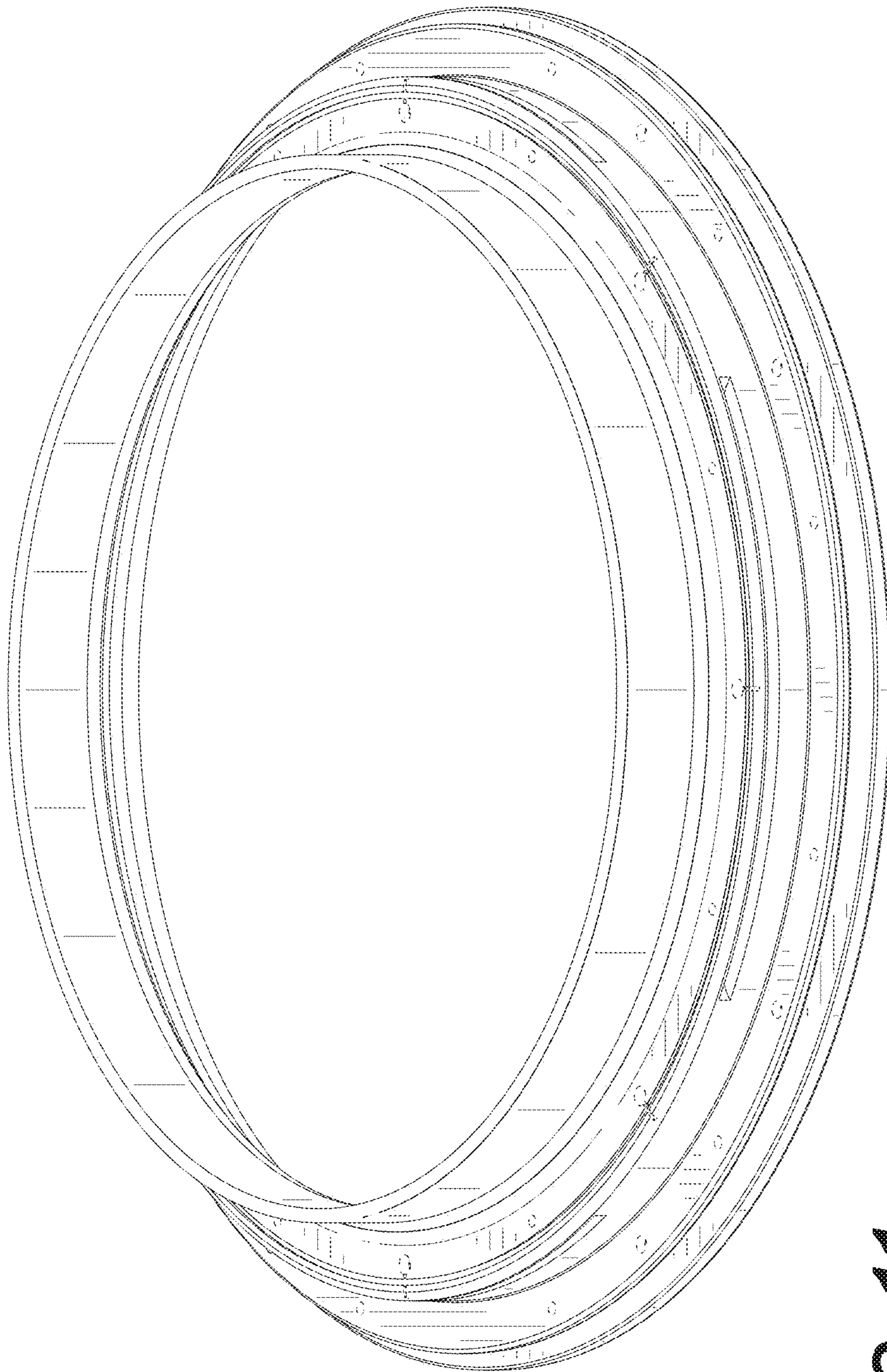


FIG. 11

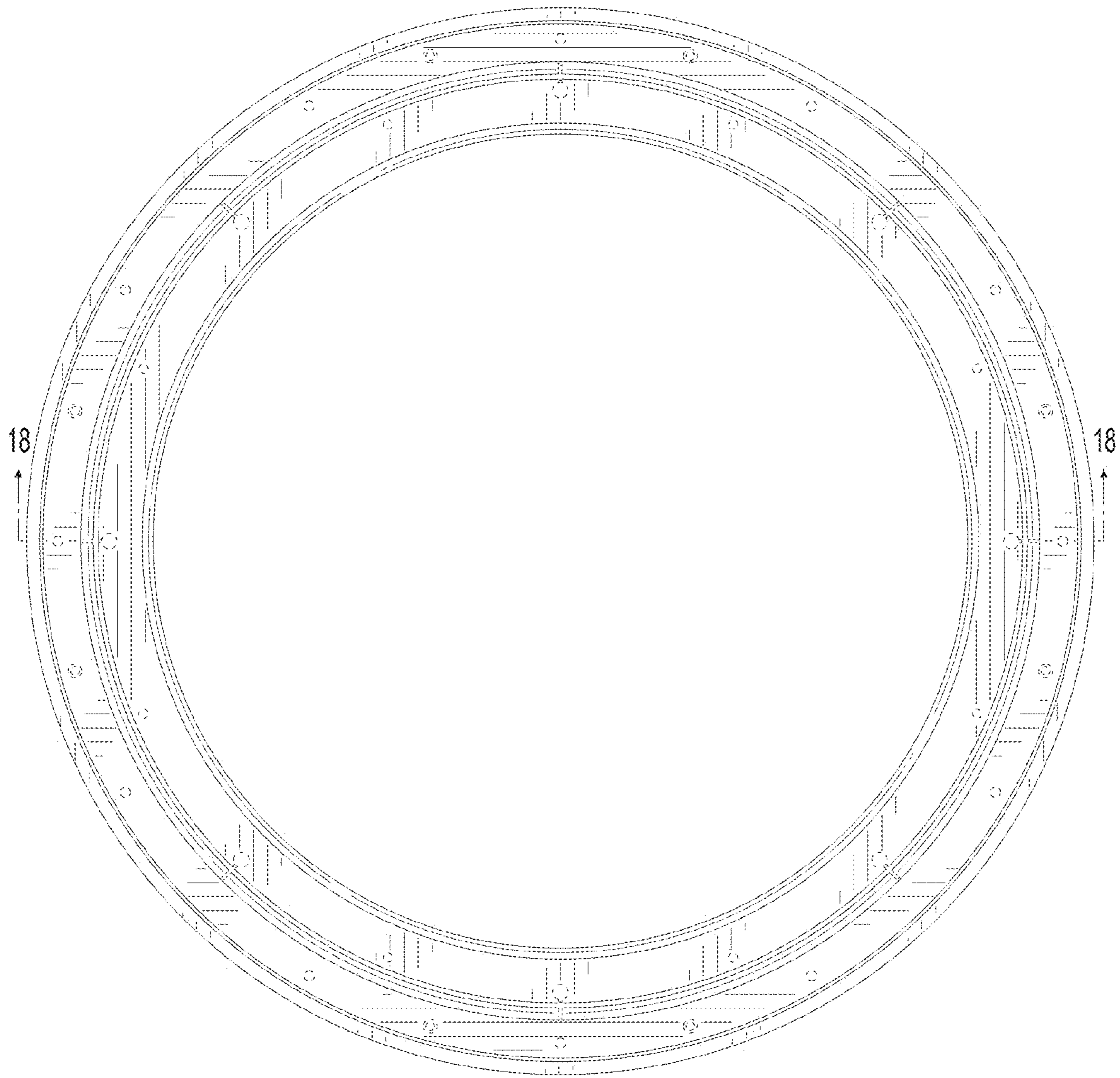


FIG. 12

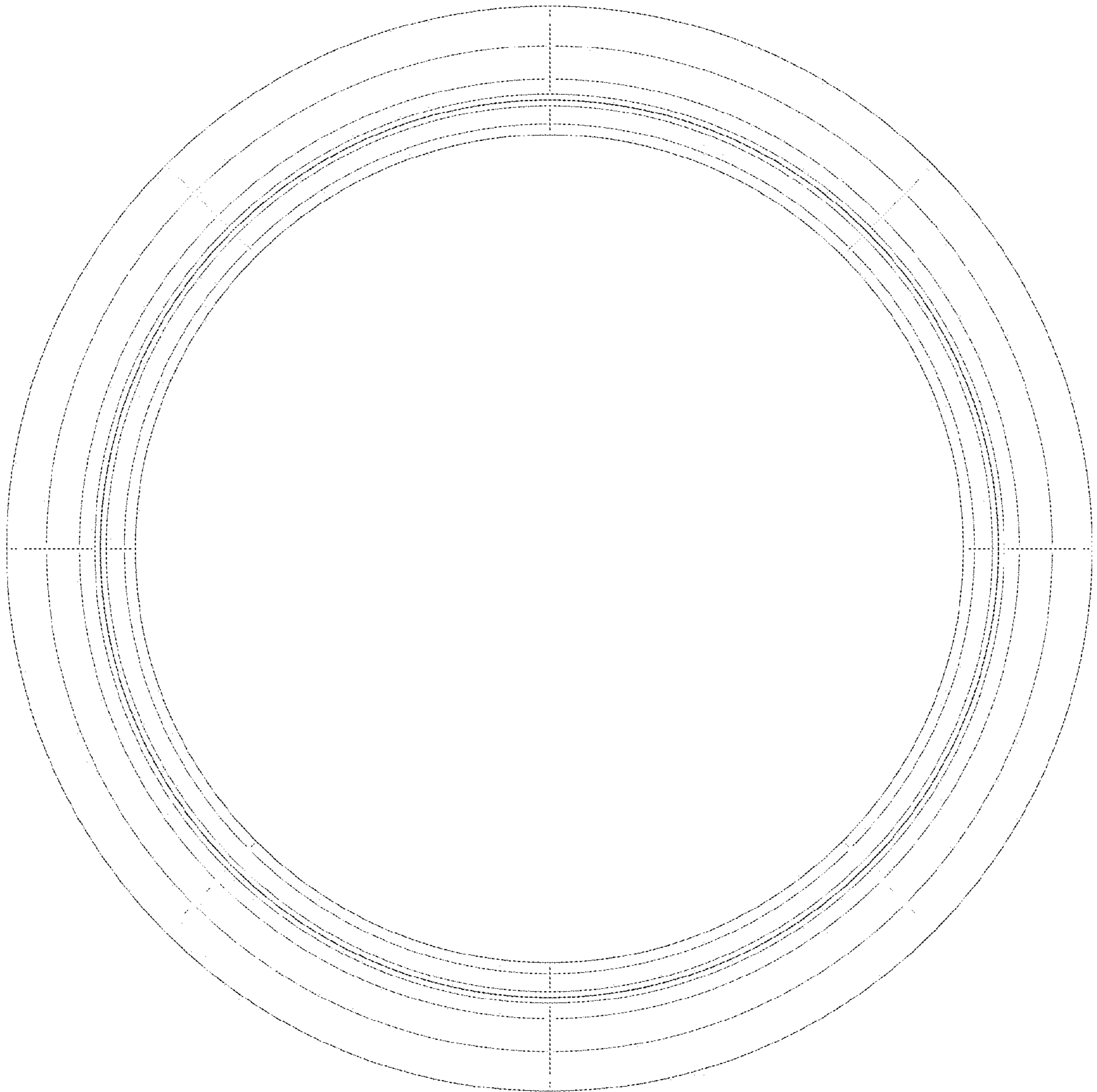


FIG. 13

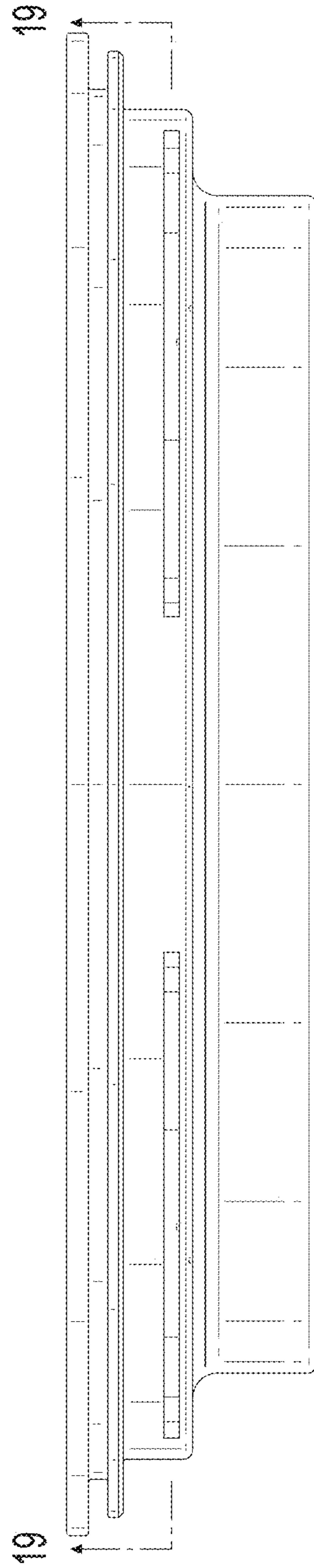


FIG. 14

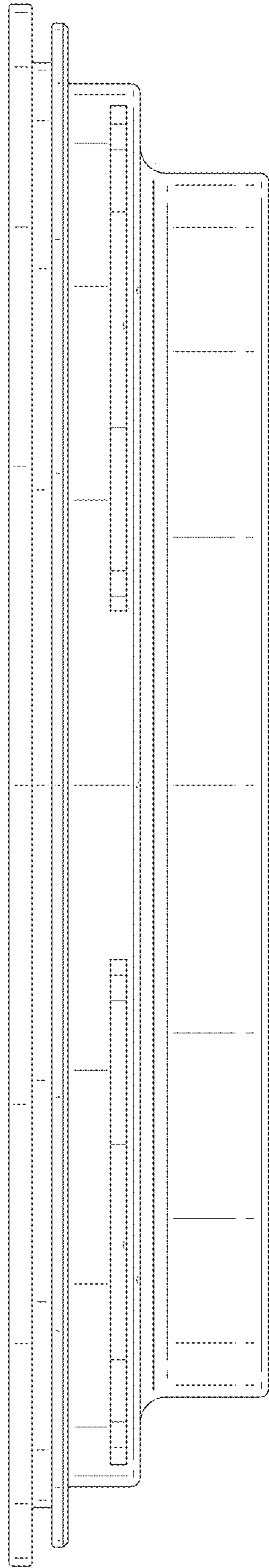


FIG. 15

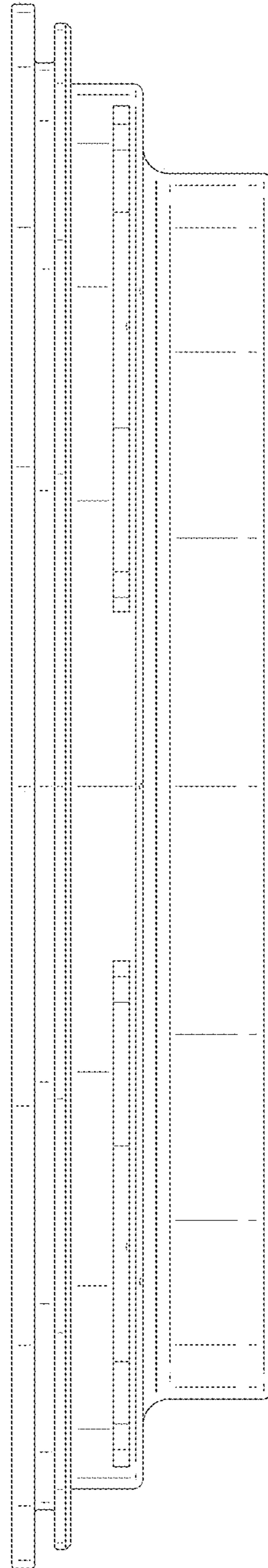


FIG. 16

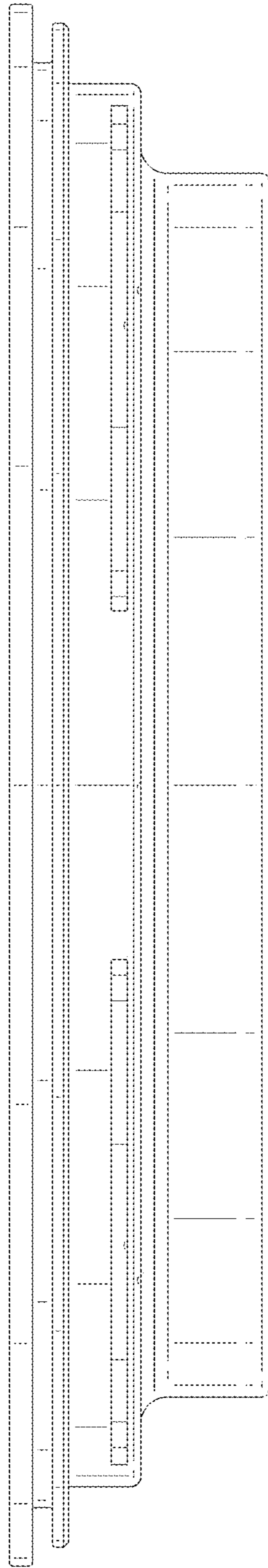


FIG. 17

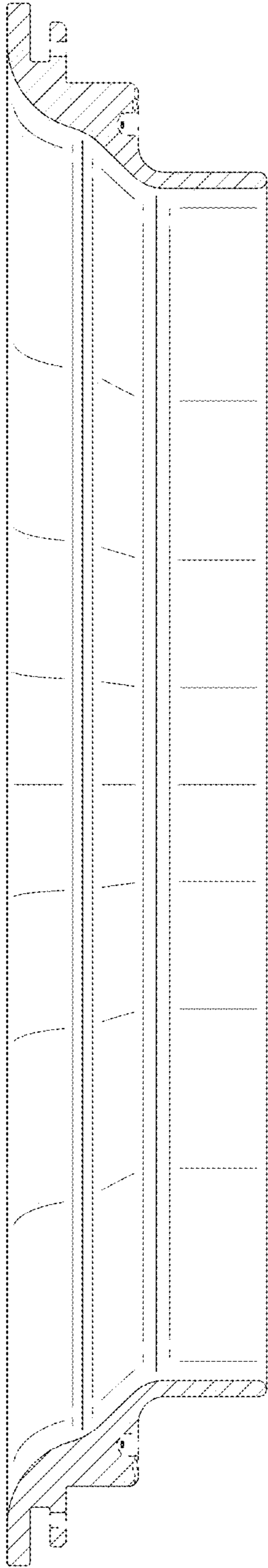


FIG. 18

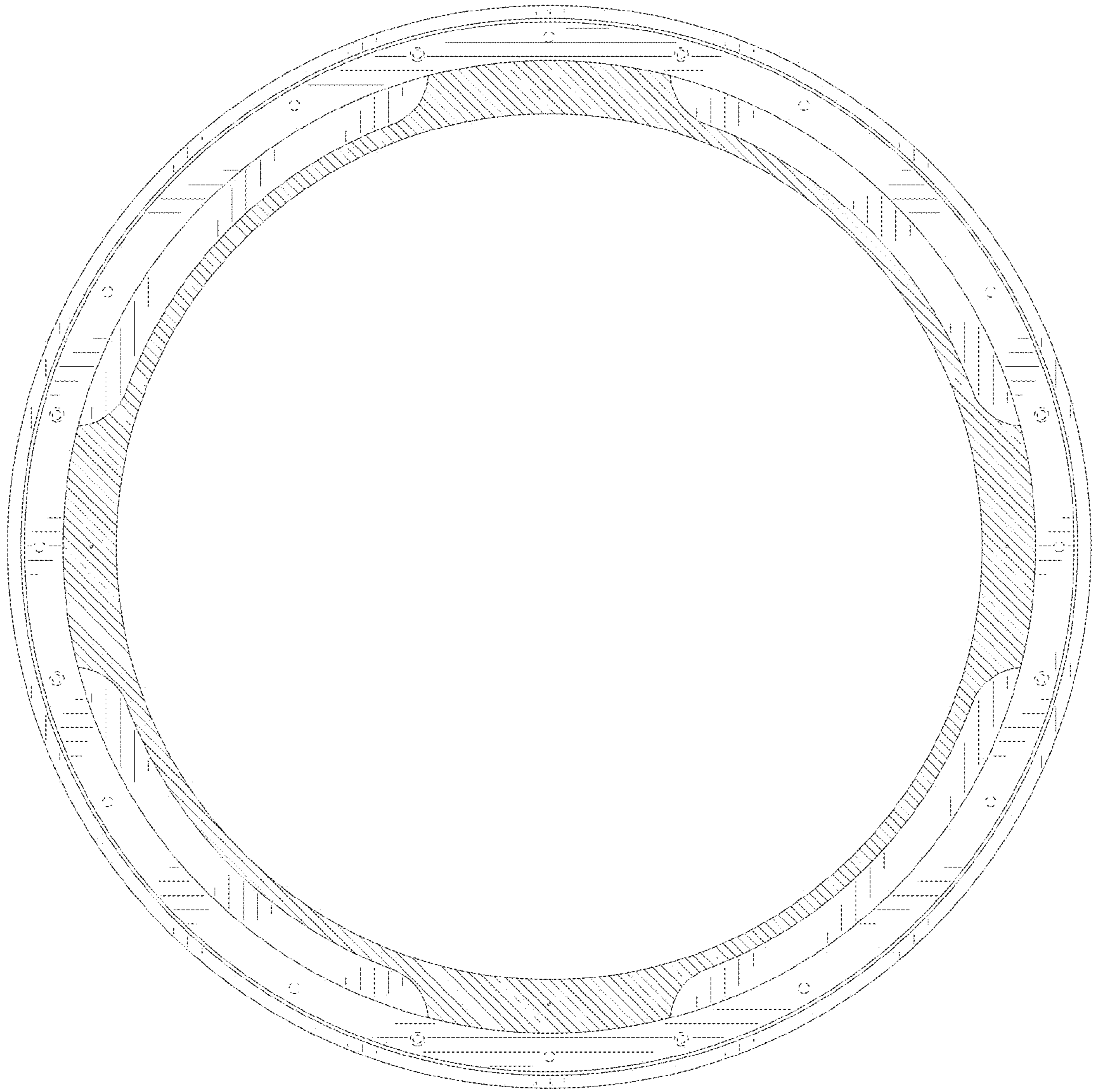


FIG. 19